

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L7	65065	CMP or "chemical mechanical polishing"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 13:44
L8	1431	slurry same filter\$3 same recirculat\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 15:32
L9	38	7 and 8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 13:44
L10	575	slurry and filter\$3 and recirculat\$4 and abrasive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 16:24
L11	131	10 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 13:51
L12	4555	slurry and filter\$3 and mix\$4 and abrasive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 14:18
L13	730	12 and 7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 14:19
L14	685	13 and semiconductor	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 14:19

L15	676	slurry same filter\$3 same abrasive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 15:32
L16	1331	slurry and filter\$3 and (recirculat\$4 or recycl\$4) and abrasive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 16:25
L17	6372	slurry same filter\$3 same (recirculat\$4 or recycl\$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 16:24
L18	227	17 and abrasive	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/29 16:25